

# **TCD3000 Si**



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The compact and robust TCD3000 SiA (Screw-in) is ideally suited for precise, fast, and sensitive measurement of (quasi-)binary gas mixtures. The measurement is based on the principle of thermal conductivity. This technology is ideal for measuring gases with significantly different thermal conductivities, such as  $H_2$  and  $O_2$ .

#### **Our Advantages:**

- Revolutionary precision in hydrogen concentration measurement: Discover our gas measuring devices with industry-leading **response time of 30 ms** and a measurement range from a **few ppm to 100 vol.** %
- Unrivalled robustness for demanding environments: Our devices **resist condensate and water without damage**, provide precise measurements up to a pressure of **200 bar**, and are optimized for use in humid environments ideal for electrolysers, fuel cells, and other hydrogen applications.
- Maximum safety, minimal maintenance: Increase your work safety with our fast and reliable explosion level monitoring. Our devices are a long-term investment with a lifespan of up to 10 years.
- Adaptability meets economy: Save costs and space with our versatile gas measuring devices that can measure a wide variety of gas mixtures without additional sample preparation.

TCD3000 Si SPECIFICATIONS					
Dimensions with connections; Weight	H=80 mm, D=40 mm; G1/2"; SW36; ~250g				
Power Supply	24 VDC ±25 %, 5 W				
Digital Output	RS485, Baud rate 38400 / Data 8bit				
Analog Output	4-20 mA, 3-wire connection				
Ambient temperature range	-40°C – +90°C (+125°C)				
Warm-up Time	<1 min.				
Flow Rate	0 – 10 m/s				
Gas Pressure (absolute)	0,8 – 200 Bara				
T90-Time	<1s				
Noise	< 50 ppm				
Drift at zero point	< 100 ppm per week				
Repeatability	< 50 ppm				
Error due to change of ambient temperature	< 50 ppm per 10°C				
Flow Influence	< 50 ppm per 1 m/s				
Pressure Dependency (above 800 hPa)	< 50 ppm per 10hPa				
All data refer to the measuring range 0.5 vol.% $H_2$ in $N_2$					



# MOST REQUESTED MEASUREMENT COMPONENTS AND RANGES

Measuring gas	Carrier gas	Basis range	Smallest range
Hydrogen (H <sub>2</sub> )	Oxygen (O <sub>2</sub> )	0 – 100 % *	0 – 0,5 %
Oxygen (O <sub>2</sub> )	Hydrogen (H₂)	0 – 100 % *	0 – 1,0 %
Hydrogen (H <sub>2</sub> )	Nitrogen (N <sub>2</sub> ) or air	0 – 100 %	0 – 0,5 %
Nitrogen (N <sub>2</sub> )	Hydrogen (H₂)	0 – 100 %	0 – 2,0 %
Hydrogen (H₂)	Argon (Ar)	0 – 100 %	0 – 0,5 %
Hydrogen (H <sub>2</sub> )	Helium (He)	20 – 100 %	-
Hydrogen (H <sub>2</sub> )	Methane (CH4)	0 – 100 %	0 – 0,5 %
Hydrogen (H <sub>2</sub> )	Carbon dioxide (CO <sub>2</sub> )	0 – 100 %	0 – 0,5 %
Helium (He)	Nitrogen (N <sub>2</sub> ) or air	0 – 100 %	0 – 0,8 %
Helium (He)	Argon (Ar)	0 – 100 %	0 – 0,5 %
Methane (CH <sub>4</sub> )	Nitrogen (N <sub>2</sub> ) or air	0 – 100 %	0 – 2,0 %
Methane (CH <sub>4</sub> )	Argon (Ar)	0 – 100 %	0 – 1,5 %
Oxygen (O <sub>2</sub> )	Nitrogen (N <sub>2</sub> )	0 – 100 %	0 – 15,0 %
Oxygen (O <sub>2</sub> )	Argon (Ar)	0 – 100 %	0 – 2,0 %
Oxygen (O <sub>2</sub> )	Carbon dioxide (CO <sub>2</sub> )	0 – 100 %	0 – 3,0 %
Nitrogen (N <sub>2</sub> )	Argon (Ar)	0 – 100 %	0 – 3,0 %
Carbon dioxide (CO <sub>2</sub> )	Nitrogen (N <sub>2</sub> ) or air	0 – 100 %	0 – 3,0 %
Carbon dioxide (CO <sub>2</sub> )	Argon (Ar)	0 - 60 %	0 – 10,0 %
Argon (Ar)	Carbon dioxide (CO <sub>2</sub> )	40 - 100 %	_
Argon (Ar)	Oxygen (O <sub>2</sub> )	0 – 100 %	0 – 3,0 %

TCD technology also allows to perform the measurements of the following industrial gases: SF<sub>6</sub>, NO<sub>2</sub>, Neon, Krypton, Xenon, Deuterium etc.

<sup>\*</sup> correspondent safety measures must be taken by the client in the application with explosive gas mixtures

GENE	RAL AP	PLICATION AREAS	APPLICATION EXAMPLES		
	∞₽▲	Oil & gas, petrochemicals, chemicals	Hydrogen measurement in electrolysis	O <sub>2</sub> in H <sub>2</sub>	Upper Explosion Limit (UEL)
		如 and synthetics	Oxygen measurement in electrolysis	H <sub>2</sub> in O <sub>2</sub>	Lower Explosion Limit (LEL), with high moisture content
		Gas chromatographs  Air separators and pure gas production	H <sub>2</sub> contamination in electrolysis, fuel cells, and semiconductor industry	H <sub>2</sub>	99-100 vol.%, H <sub>2</sub> Quality 4.0
<b>O</b>		Detection of gas leakages	Exhaust gas measurement in fuel cells	H₂ in Air	LEL monitoring with very high water content
<b>O</b>		Pharmacy	H <sub>2</sub> injection into the natural gas network	H₂ in Natural Gas	0-100 vol.%, mixing control
d		Food industry	Decomposition and synthesis of ammonia	H <sub>2</sub> in N <sub>2</sub> + NH <sub>3</sub>	0-100 vol.%, process control
<b>o</b>	##	Metals, minerals, pulp and paper	Turbogenerators in power generation	H <sub>2</sub> in Luft, H <sub>2</sub> in CO <sub>2</sub> (Ar), CO <sub>2</sub> (Ar) in Air	Monitoring of UEL, draining and filling process
	# A	Power generation	Pure gas production and incoming goods inspection	H <sub>2</sub> , He, CH <sub>4</sub> , O <sub>2</sub> , N <sub>2</sub> , CO <sub>2</sub> , Ar	Identification of the quality of produced and delivered gases
0	Environmental technology	Industrial applications	H <sub>2</sub> in N <sub>2</sub>	0-10 vol.%, systems for the production and monitoring of forming gas	
			Safety monitoring	H₂ in Air	UEL, analysis of hydrogen dispersion in facilities and buildings



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